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Citation: [Surface Science Spectra](#) **24**, 024001 (2017); doi: 10.1116/1.4998018

View online: <http://dx.doi.org/10.1116/1.4998018>

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Published by the [American Vacuum Society](#)



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Vanadium, niobium and tantalum by XPS

Pakpoom Buabthong, Natalie Becerra Stasiewicz, Slobodan Mitrovic,^{a)} and Nathan S. Lewis^{a)}

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(Received 16 March 2017; accepted 20 June 2017; published 22 August 2017)

We present high-resolution XPS spectra of elemental vanadium, niobium and tantalum sputter-cleaned by Ar⁺ ions. The energy scales are shown without applying any corrections, and the position of the Fermi level was verified to be at zero binding energy within better than 0.1 eV, as determined from the Fermi edge measurement. © 2017 American Vacuum Society.

[<http://dx.doi.org/10.1116/1.4998018>]

Keywords: XPS; vanadium; niobium; tantalum

Accession #s: 01408, 01409, 01410

Technique: XPS

Host Material: #01408: vanadium;
 #01409: niobium; #01410: tantalum

Instrument: Kratos Analytical Axis
 Nova

Major Elements in Spectra: V, Nb,
 Ta

Minor Elements in Spectra: Ar, O

Published Spectra: 23

Spectra in Electronic Record: 28

Spectral Category: reference

INTRODUCTION

Combinatorial science deals with complex materials with compositions containing many elements, often with overlapping features in their XPS spectra. At the Joint Center for Artificial Photosynthesis, we explore such material spaces in high-throughput, to find the most suitable catalysts and light absorbers for direct conversion of sunlight into fuels. In order to develop the tools for reliable determination of surface chemical compositions by XPS, we have acquired consistent and comparable reference spectra in high-resolution for all measurable core levels of a particular pure element, or their stable compounds. The data are acquired on the same machine, with the same pass energy and x-ray power; and they contain all measurable loss features. In this publication, we present the results for group five elements.

SPECIMEN DESCRIPTION (ACCESSION #01408, 1 OF 3) —

Host Material: vanadium

CAS Registry #: 7440-62-2

Host Material Characteristics: homogeneous; solid; unknown crystallinity; conductor; metal

Chemical Name: V

Source: Sigma-Aldrich, Co.

Host Composition: vanadium 99.7%

Form: foil

Lot #: MKBP7987V

Structure: bcc

History & Significance: 99.7% pure vanadium

As Received Condition: as received from supplier (polished)

Analyzed Region: not specified

Ex Situ Preparation/Mounting: The foil was cleaned by wiping with isopropyl alcohol, and then mounted under the conductive contact of the sample platen.

In Situ Preparation: Surface was ion-sputtered until no O 1s or C 1s were visible in a high pass energy, wide scan.

Pre-Analysis Beam Exposure: no exposure prior to data acquisition

Charge Control: no charge control applied

Temp. During Analysis: 300 K

Pressure During Analysis: $<5 \times 10^{-7}$ Pa

SPECIMEN DESCRIPTION (ACCESSION #01409, 2 OF 3) —

Host Material: niobium

CAS Registry #: 7440-03-1

Host Material Characteristics: unknown homogeneity; solid; unknown crystallinity; conductor; metal

Chemical Name: Nb

Source: Alfa Aesar

Host Composition: Nb 99.95% (metals basis excluding Ta)

Form: not specified

Lot #: C03Q25

As Received Condition: as received from supplier

Analyzed Region: not specified

Ex Situ Preparation/Mounting: Mounted on conductive tape on the sample platen in electrical contact with the analyzer.

In Situ Preparation: Surface was ion-sputtered until no O 1s or C 1s were visible in a high pass energy, wide scan.

Pre-Analysis Beam Exposure:

Charge Control: none

Temp. During Analysis: 300 K

Pressure During Analysis: $<5 \times 10^{-7}$ Pa

SPECIMEN DESCRIPTION (ACCESSION #01410, 3 OF 3) —

Host Material: tantalum

CAS Registry #: 7440-25-7

Host Material Characteristics: homogeneous; solid; unknown crystallinity; conductor; metal

Chemical Name: Ta

Source: Sigma-Aldrich, Co.

Host Composition: tantalum 99.9% trace metal basis

^{a)}Author to whom correspondence should be addressed.

Form: foil, thickness 0.25 mm

Lot #: MKBW6466V

As Received Condition: as received from supplier (polished)

Analyzed Region: not specified

Ex Situ Preparation/Mounting: sample was wiped with isopropanol

In Situ Preparation: Surface was ion-sputtered until no O 1s or C 1s were visible in a high pass energy, wide scan.

Pre-Analysis Beam Exposure:

Charge Control: none

Temp. During Analysis: 300 K

Pressure During Analysis: $<5 \times 10^{-7}$ Pa

INSTRUMENT DESCRIPTION

Manufacturer and Model: Kratos Analytical Axis Nova

Analyzer Type: Other

Number of Detector Elements: 127

Analyzer Description: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)

INSTRUMENT PARAMETERS COMMON TO ALL SPECTRA

■ **Spectrometer**

Analyzer Mode: constant pass energy

Throughput ($T=E^M$): N=See comment below

Throughput Comment: The energy dependence is recorded in a file at the time of data acquisition.

Excitation Source Window: Aluminum K-alpha monochromatic excitation at 1486.6 eV

Excitation Source: Al K_{α} , monochromatic

Source Energy: 1486.6 eV

Source Strength: 150 W

Signal Mode:

■ **Geometry**

Incident Angle: not specified

Source to Analyzer Angle: not specified

Emission Angle: not specified

Specimen Azimuthal Angle: 0°

Acceptance Angle from Analyzer Axis: 35.5°

■ **Ion Gun**

Manufacturer and Model: Kratos Analytical Ltd. Minibeam IV

Energy: 4000 eV

Current: 0.120 mA/cm²

Current Measurement Method: biased stage

Sputtering Species: Ar⁺

Spot Size (unrastered): 500 μ m

Raster Size: 2000 μ m \times 2000 μ m

Azimuthal Angle: 0°

Comment: no rotation

DATA ANALYSIS METHOD

Energy Scale Correction: No energy shifting has been applied to any spectra.

Recommended Energy Scale Shift: We do not recommend any energy scale shifts.

Peak Shape and Background Method:

Quantitation Method:

ACKNOWLEDGMENTS

This material is based upon work performed by the Joint Center for Artificial Photosynthesis, a DOE Energy Innovation Hub, supported through the Office of Science of the U.S. Department of Energy under Award Number DE-SC0004993.

SPECTRAL FEATURES TABLE							
Spectrum ID #	Element/ Transition	Peak Energy (eV)	Peak Width FWHM (eV)	Peak Area (eV × cts/s)	Sensitivity Factor	Concentration (at. %)	Peak Assignment
01408-02	V 2p _{3/2}	506.60	0.60	24570	1.41	...	V
01408-02	V 2p _{1/2}	514.15	0.63	11990	0.71	...	V
01408-02	O 1s	525.49	1.91	1970	0.78	...	O
01408-03	V 3p	31.43	0.917	3910	0.274	...	V
01408-04	V 3s	60.30	1.99	2150	0.131	...	V
01408-05	V 2s	620.58	6.11	8540	0.673	...	V
01409-02	Nb 3d _{5/2}	202.26	0.433	28130	1.75	...	Nb
01409-02	Nb 3d _{3/2}	204.99	0.433	14070	1.17	...	Nb
01409-04	Nb 3p _{3/2}	360.35	2.181	38020	1.75	...	Nb
01409-04	Nb 3p _{1/2}	374.86	2.181	15410	0.88	...	Nb
01409-05	Nb 4s	56.00	4.7	1874	0.126	...	Nb
01409-05	Nb 4p _{3/2}	30.60	1.13	3907	0.254	...	Nb
01409-05	Nb 4p _{1/2}	32.45	1.16	1954	0.127	...	Nb
01409-06	Nb 3s	466.55	6.76	6250	0.393	...	Nb
01410-02	Ta 4f _{7/2}	21.56	0.39	22000	1.761	...	Ta
01410-02	Ta 4f _{5/2}	23.48	0.39	16500	1.321	...	Ta
01410-02	Ta 4f _{7/2}	23.06	1.06	2865	1.761	...	Ta-O
01410-02	Ta 4f _{5/2}	24.98	1.06	2150	1.321	...	Ta-O
01410-03	Ta 4d _{5/2}	226.33	5.69	46830	2.17	...	Ta
01410-03	Ta 4d _{3/2}	237.49	5.70	31380	1.08	...	Ta
01410-04	Ta 4p _{3/2}	401.02	6.9	26110	2.170	...	Ta
01410-04	Ta 4p _{1/2}	462.20	6.9	13055	1.085	...	Ta
01410-04	Ta 4p _{3/2}	420.82	16.16	13690	2.170	...	Ta-O
01410-04	Ta 4p _{1/2}	482.00	16.16	6820	1.085	...	Ta-O
01410-04	O 1s	530.80	1.55	1340	0.78	...	O
01410-05	Ta 4s	563.02	8.135	5605	0.244	...	Ta
01410-06	Ta 5s	68.75	8.88	2840	0.227	...	Ta
01410-06	Ta 5p _{3/2}	32.51	1.60	...	0.262	...	Ta
01410-06	Ta 5p _{1/2}	43.71	7.51	10700	0.131	...	Ta

ANALYZER CALIBRATION TABLE

Spectrum ID #	Element/ Transition	Peak Energy (eV)	Peak Width FWHM (eV)	Peak Area (eV × cts/s)	Sensitivity Factor	Concentration (at. %)	Peak Assignment
1408-07 ^a	V Fermi edge	0	Fermi edge
1409-08 ^b	Nb Fermi edge	0
1410-08 ^c	Ta Fermi edge	0
1411-01 ^d	Ag 3d _{5/2}	368.24	0.52	129360	3d _{5/2}
1411-02 ^e	Ag 3d _{5/2}	367.69	2.00	10393	3d _{5/2}

^a Fermi function fit gives position of the Fermi level at E = 0.056 (0.005) eV, and broadening that includes thermal and instrumental broadening T = 0.094 (0.004) eV, which includes thermal broadening and instrument resolution.

^b Fermi function fit gives position of the Fermi level at E = 0.073 (0.004) eV, and broadening that includes thermal and instrumental broadening T = 0.093 (0.004) eV, which includes thermal broadening and instrument resolution.

^c Fermi function fit gives position of the Fermi level at E = 0.023 (0.003) eV, and broadening that includes thermal and instrumental broadening T = 0.094 (0.003) eV, which includes thermal broadening and instrument resolution.

^d Ag 3d_{5/2} calibration peak with passing energy of 10 eV.

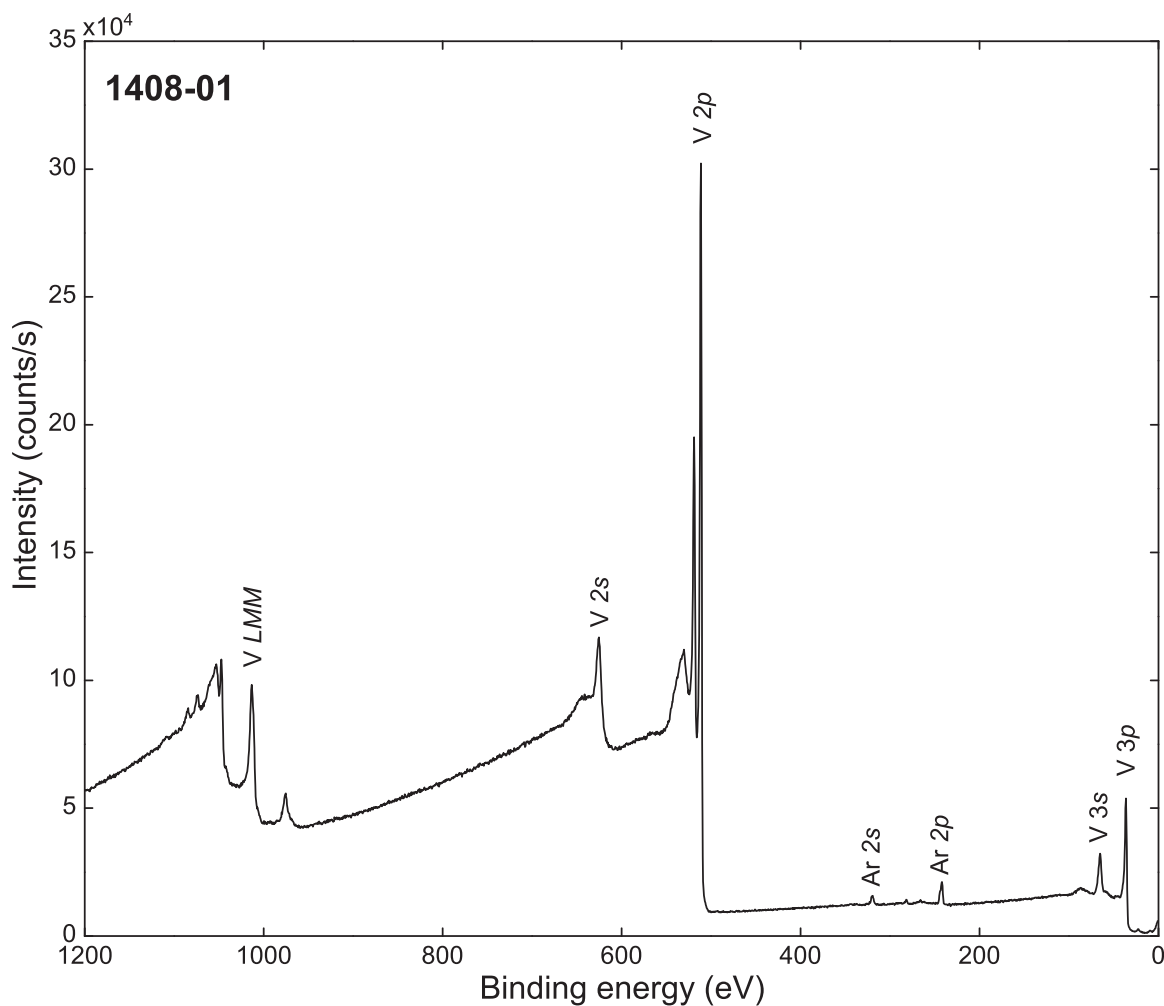
^e Ag 3d_{5/2} calibration peak with passing energy of 160 eV.

GUIDE TO FIGURES					
Spectrum (Accession) #	Spectral Region	Voltage Shift*	Multiplier	Baseline	Comment #
1408-01	survey	0	1	0	1
1408-02	O 1s, V 2p 1/2, V 2p 3/2	0	1	0	1
1408-03	V 3p	0	1	0	1
1408-04	V 3s	0	1	0	1
1408-05	V 2s	0	1	0	1
1408-06	V LMM	0	1	0	1
1408-07	V valence band	0	1	0	1
1408-07	V valence band, fit	0	1	0	1
1409-01	survey	0	1	0	2
1409-02	Nb 3d _{3/2} , Nb 3d _{5/2}	0	1	0	2
1409-03	Nb 3d _{5/2} , Nb 3d _{3/2}	0	1	0	2
1409-04	Nb 3p _{1/2} , Nb 3p _{3/2}	0	1	0	2
1409-05	Nb 4s, Nb 4p _{1/2} , Nb 4p _{3/2}	0	1	0	2
1409-06	Nb 3s	0	1	0	2
1409-07	Nb MNN	0	1	0	2
1409-08	Nb valence band	0	1	0	2
1409-08	Nb valence band, fit	0	1	0	2
1410-01	survey	0	1	0	3
1410-02	Ta 4f _{5/2} , Ta 4f _{7/2}	0	1	0	3
1410-03	Ta 4d _{3/2} , Ta 4d _{5/2}	0	1	0	3
1410-04	O 1s, Ta 4p _{1/2} , Ta 4p _{3/2}	0	1	0	3
1410-05	Ta 4s	0	1	0	3
1410-06	Ta 5s, Ta 5p _{1/2} , Ta 5p _{3/2}	0	1	0	3
1410-07	Ta NNN	0	1	0	3
1410-08	Ta valence band	0	1	0	3
1410-08	Ta valence band, fit	0	1	0	3
1411-01 [NP]**	Ag 3d _{5/2} , Ag 3d _{3/2}	0	1	0	4
1411-02 [NP]	Ag 3d _{5/2} , Ag 3d _{3/2}	0	1	0	4

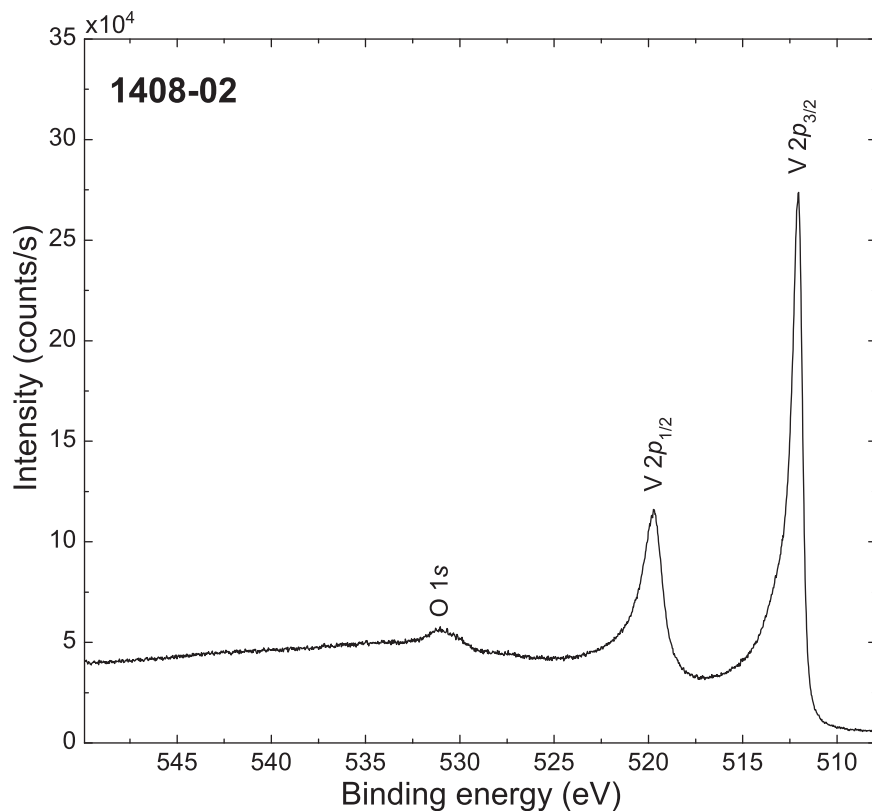
* Voltage shift of the archived (as-measured) spectrum relative to the printed figure. The figure reflects the recommended energy scale correction due to a calibration correction, sample charging, flood gun, or other phenomenon.

** [NP] signifies not published; digital spectra are archived in SSS database but not reproduced in the printed journal.

1. Vanadium foil
2. Niobium slug
3. Tantalum foil
4. Ag pellet

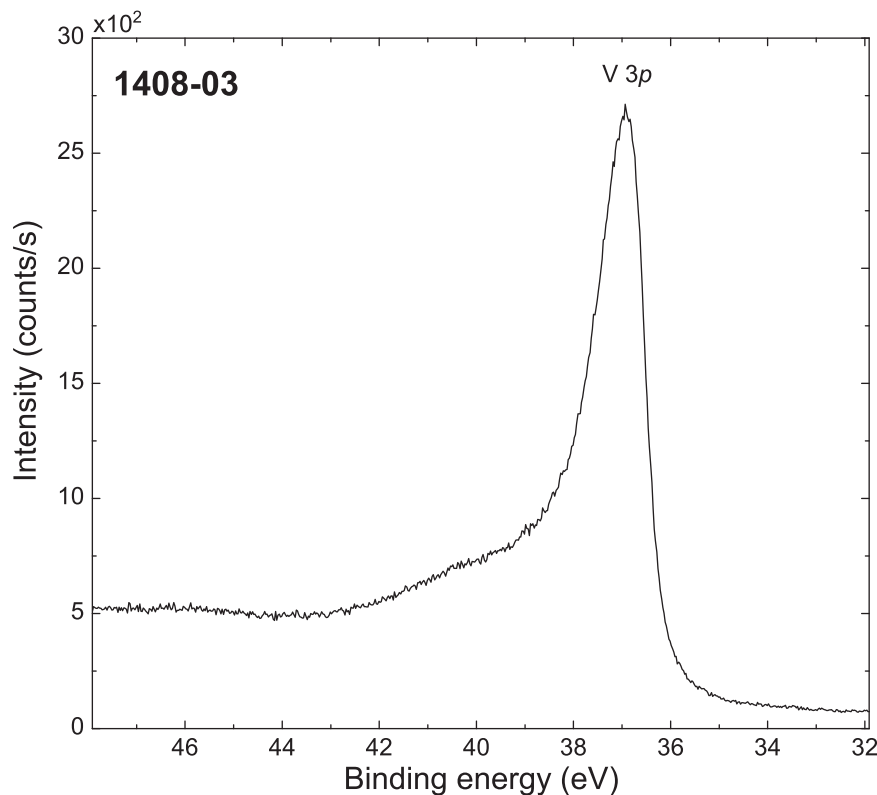


Accession #	01408-01
Host Material	vanadium
Technique	XPS
Spectral Region	survey
Instrument	Kratos Analytical Axis Nova
Excitation Source	Al K_{α} monochromatic
Source Energy	1486.6 eV
Source Strength	150 W
Source Size	not specified
Analyzer Type	Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)
Incident Angle	not specified°
Emission Angle	not specified°
Analyzer Pass Energy:	160 eV
Analyzer Resolution	2.0 eV
Total Signal Accumulation Time	3616.5 s
Total Elapsed Time	not specified
Number of Scans	3



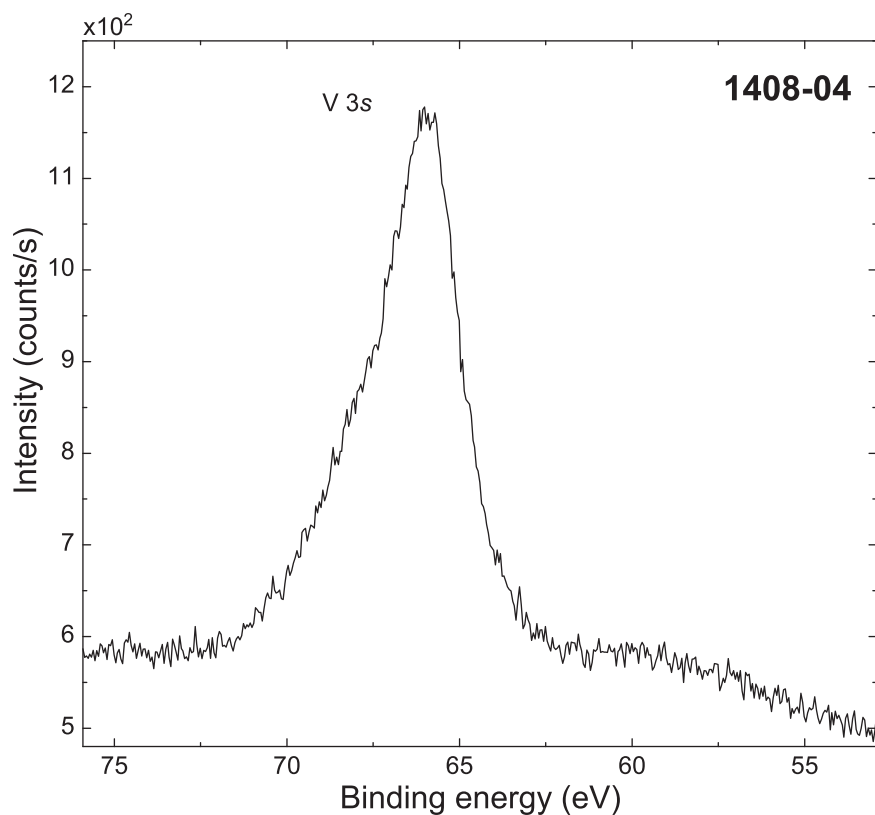
■ **Accession #:** 01408-02
 ■ **Host Material:** vanadium
 ■ **Technique:** XPS
 ■ **Spectral Region:** O 1s; V $2p_{1/2}$; V $2p_{3/2}$

Instrument: Kratos Analytical Axis Nova
 Excitation Source: Al K_{α} monochromatic
 Source Energy: 1486.6 eV
 Source Strength: 150 W
 Source Size: not specified
 Analyzer Type: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)
 Incident Angle: not specified°
 Emission Angle: not specified°
 Analyzer Pass Energy: 10 eV
 Analyzer Resolution: 0.53 eV
 Total Signal Accumulation Time: 1746 s
 Total Elapsed Time: not specified
 Number of Scans: 4



■ **Accession #:** 01408-03
 ■ **Host Material:** vanadium
 ■ **Technique:** XPS
 ■ **Spectral Region:** V 3p

Instrument: Kratos Analytical Axis Nova
 Excitation Source: Al K_{α} monochromatic
 Source Energy: 1486.6 eV
 Source Strength: 150 W
 Source Size: not specified
 Analyzer Type: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)
 Incident Angle: not specified°
 Emission Angle: not specified°
 Analyzer Pass Energy: 10 eV
 Analyzer Resolution: 0.53 eV
 Total Signal Accumulation Time: 2692.2 s
 Total Elapsed Time: not specified
 Number of Scans: 14



■ Accession #: 01408-04
 ■ Host Material: vanadium
 ■ Technique: XPS
 ■ Spectral Region: V 3s

Instrument: Kratos Analytical Axis Nova

Excitation Source: Al K_{α} monochromatic

Source Energy: 1486.6 eV

Source Strength: 150 W

Source Size: not specified

Analyzer Type: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)

Incident Angle: not specified°

Emission Angle: not specified°

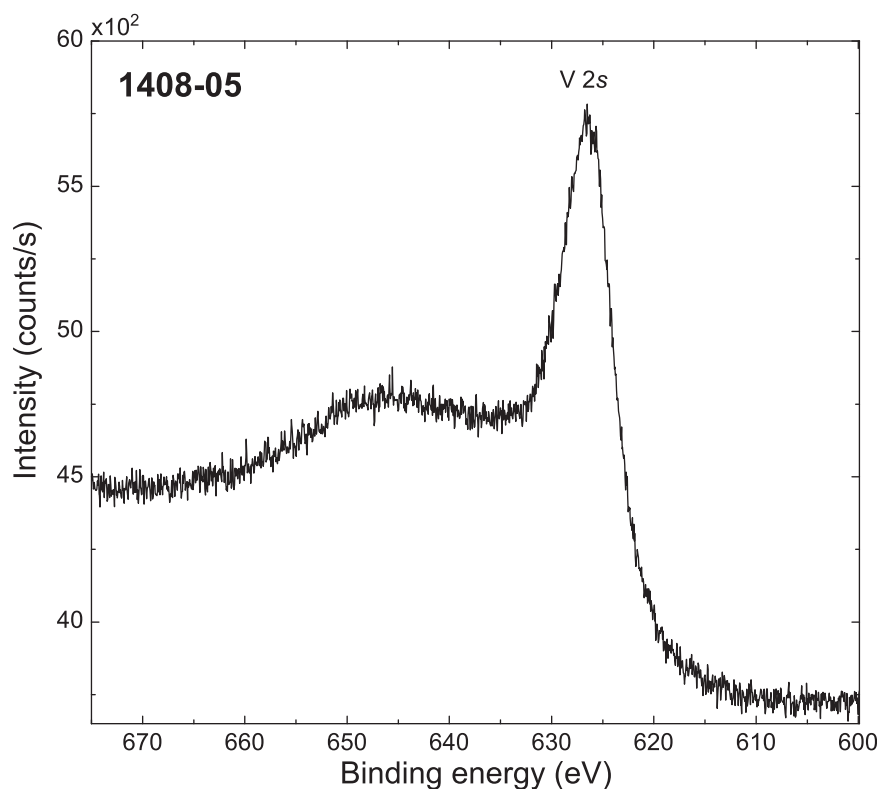
Analyzer Pass Energy: 10 eV

Analyzer Resolution: 0.53 eV

Total Signal Accumulation Time: 2766 s

Total Elapsed Time: not specified

Number of Scans: 20



■ Accession #: 01408-05
 ■ Host Material: vanadium
 ■ Technique: XPS
 ■ Spectral Region: V 2s

Instrument: Kratos Analytical Axis Nova

Excitation Source: Al K_{α} monochromatic

Source Energy: 1486.6 eV

Source Strength: 150 W

Source Size: not specified

Analyzer Type: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)

Incident Angle: not specified°

Emission Angle: not specified°

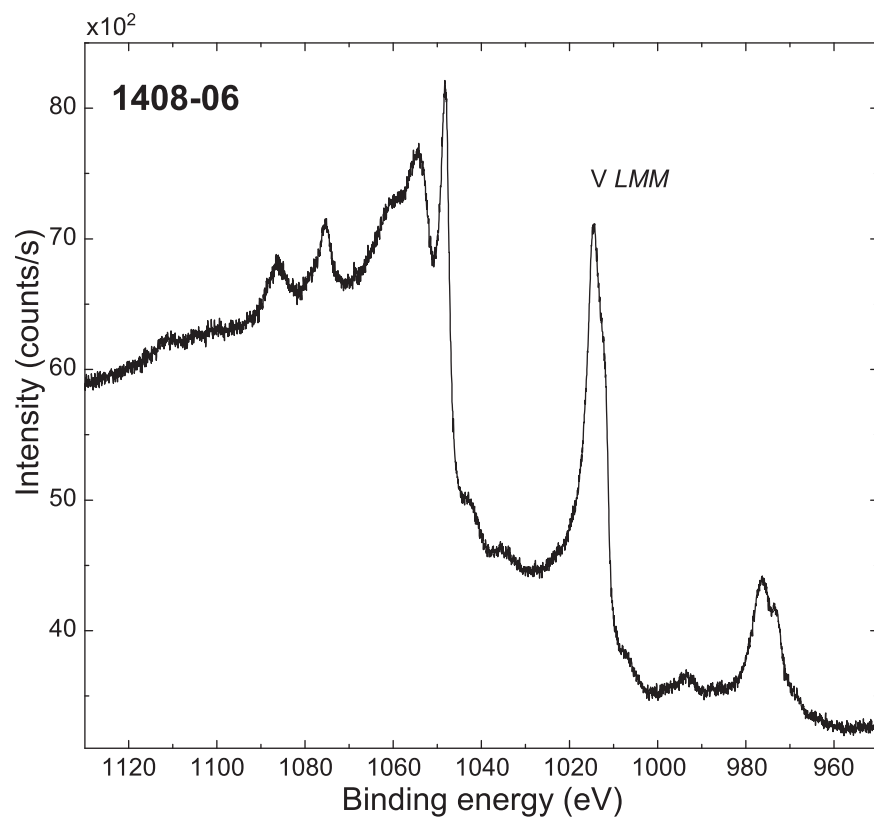
Analyzer Pass Energy: 10 eV

Analyzer Resolution: 0.53 eV

Total Signal Accumulation Time: 6404 s

Total Elapsed Time: not specified

Number of Scans: 20



■ Accession #: 01408-06
■ Host Material: vanadium
■ Technique: XPS
■ Spectral Region: V LMM

Instrument: Kratos Analytical Axis Nova

Excitation Source: Al K_{α} monochromatic

Source Energy: 1486.6 eV

Source Strength: 150 W

Source Size: not specified

Analyzer Type: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)

Incident Angle: not specified $^{\circ}$

Emission Angle: not specified $^{\circ}$

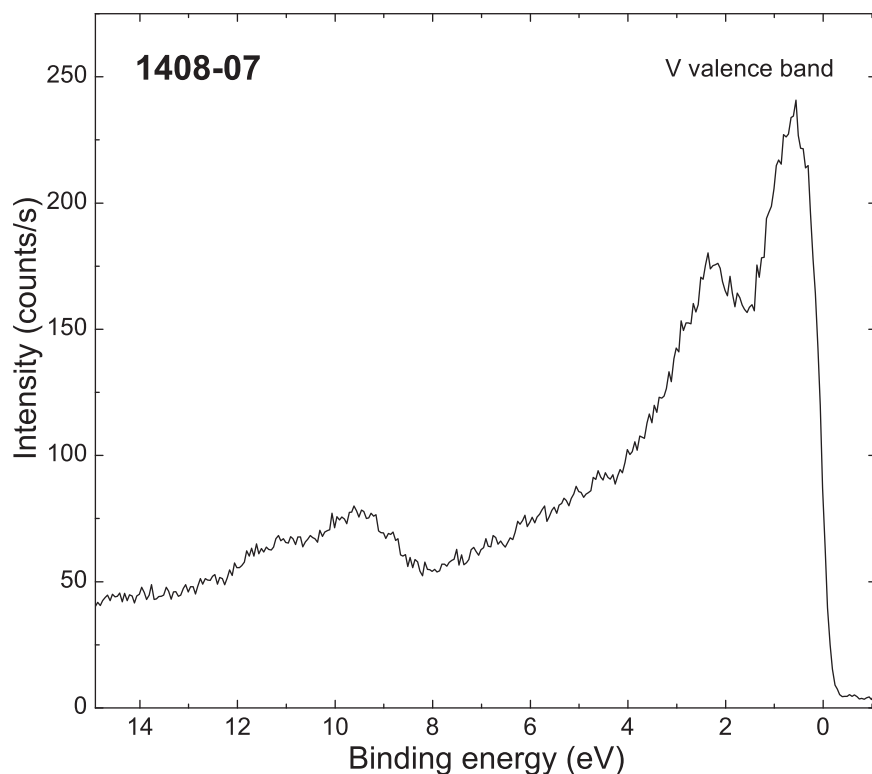
Analyzer Pass Energy: 10 eV

Analyzer Resolution: 0.53 eV

Total Signal Accumulation Time: 14404 s

Total Elapsed Time: not specified

Number of Scans: 20



■ **Accession #:** 01408-07
 ■ **Host Material:** vanadium
 ■ **Technique:** XPS
 ■ **Spectral Region:** V valence band

Instrument: Kratos Analytical Axis Nova

Excitation Source: Al K_{α}
 monochromatic

Source Energy: 1486.6 eV

Source Strength: 150 W

Source Size: not specified

Analyzer Type: Combined
 hemispherical analyzer (HSA) and
 spherical mirror analyzer (SMA)

Incident Angle: not specified°

Emission Angle: not specified°

Analyzer Pass Energy: 10 eV

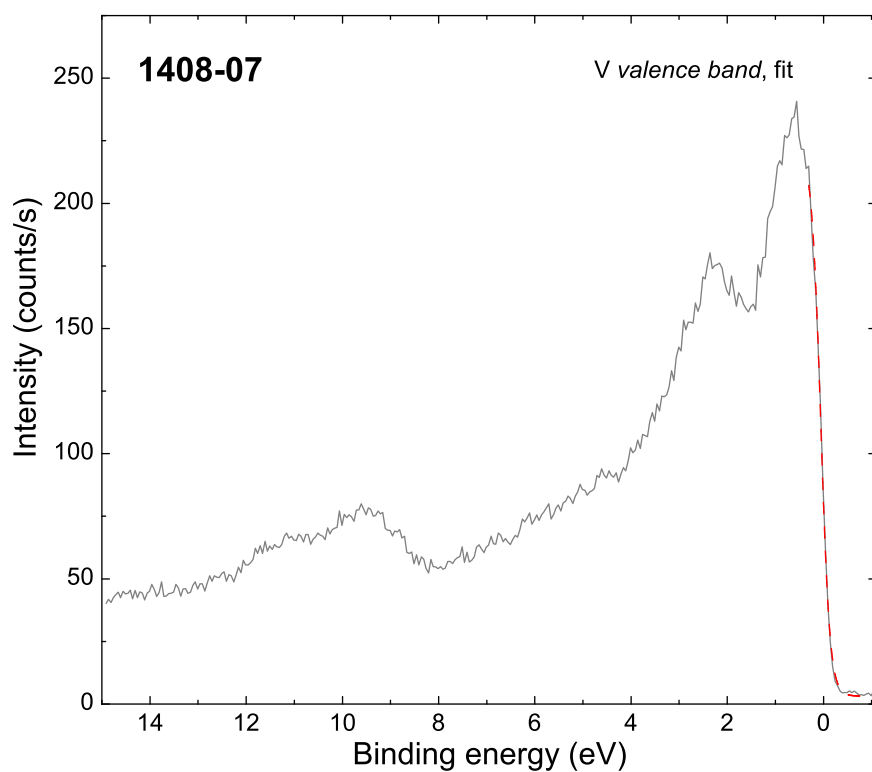
Analyzer Resolution: 0.53 eV

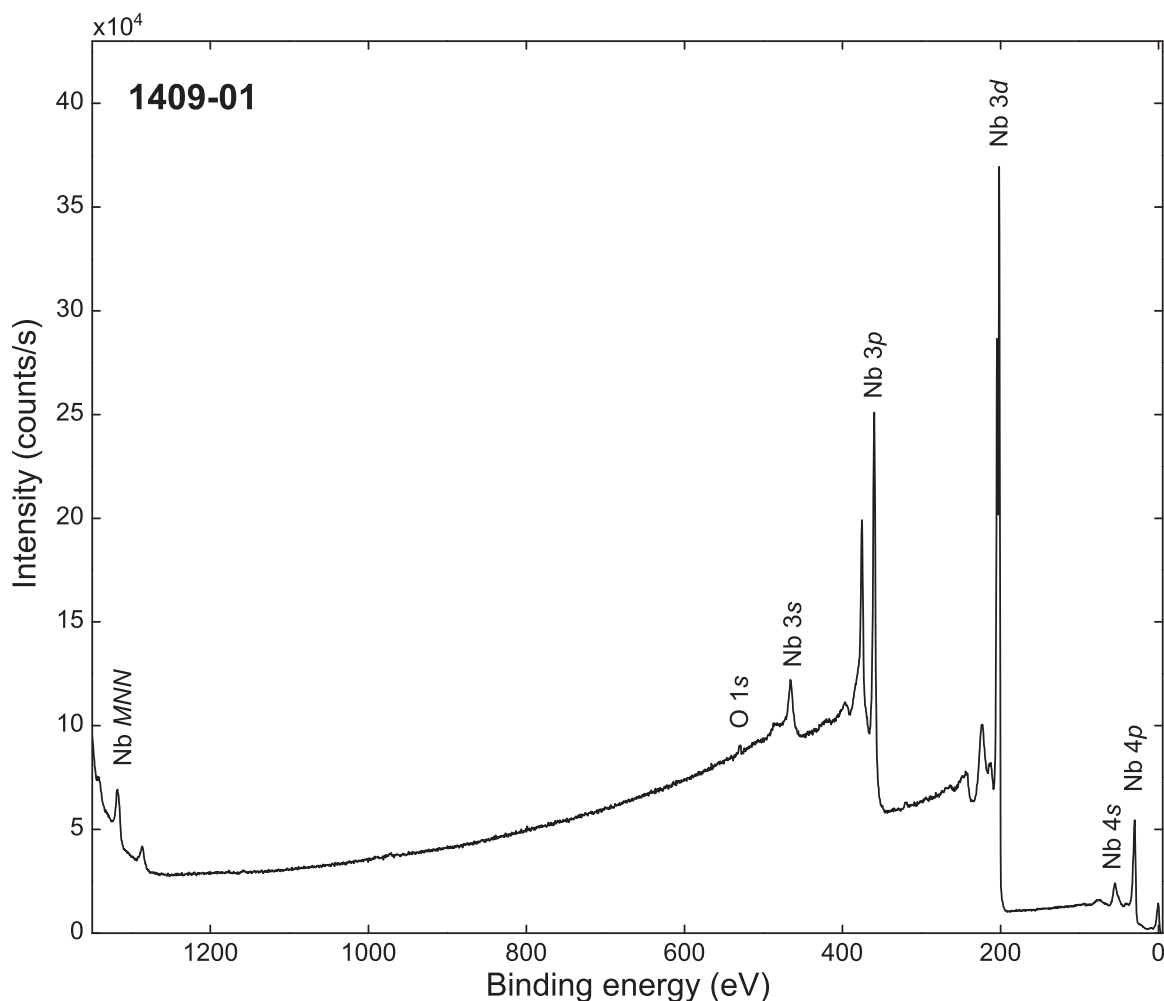
Total Signal Accumulation Time:
 4815 s

Total Elapsed Time: not specified

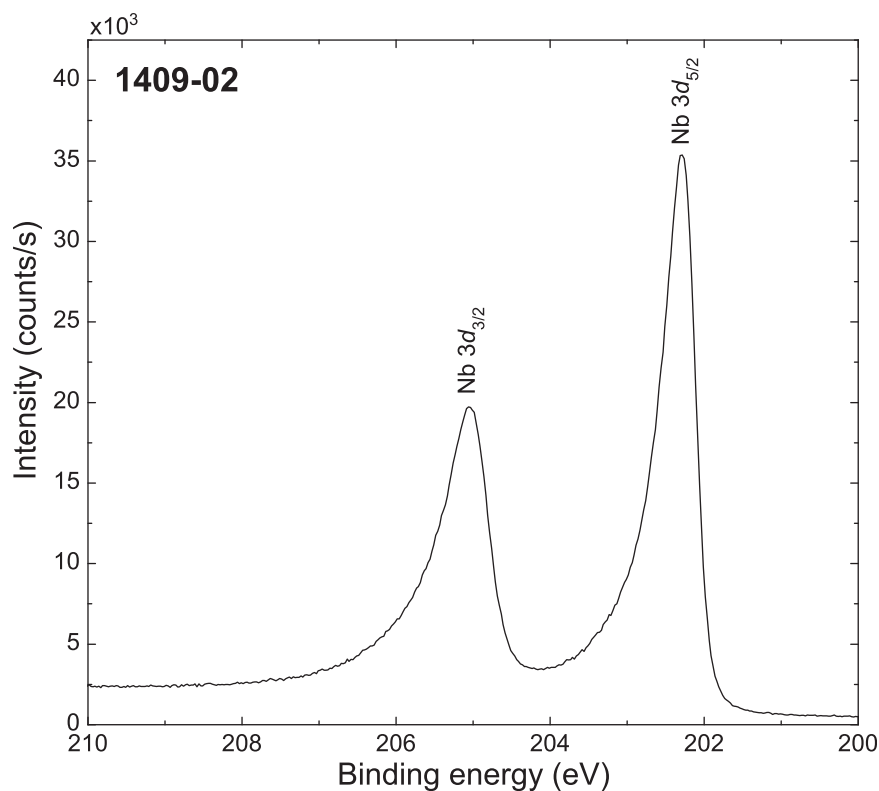
Number of Scans: 50

Comment: Following figure shows
 Fermi function fit calibration
 reference. See Analyzer Calibration
 Table entry for V Fermi edge.



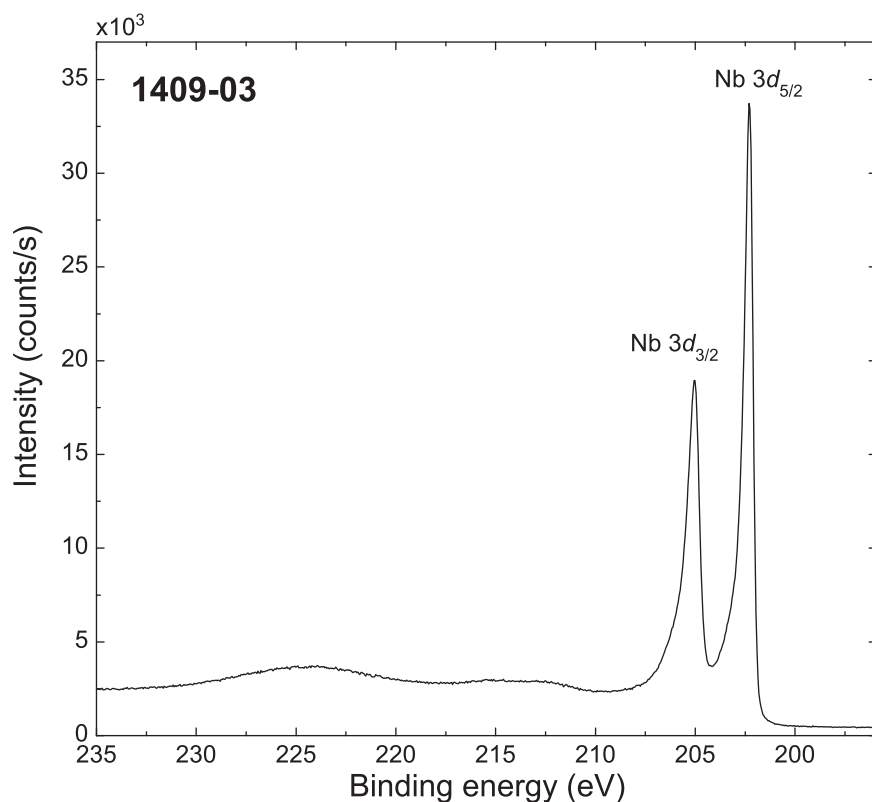


Accession #	01409-01
Host Material	niobium
Technique	XPS
Spectral Region	survey
Instrument	Kratos Analytical Axis Nova
Excitation Source	Al K_{α} monochromatic
Source Energy	1486.6 eV
Source Strength	150 W
Source Size	not specified
Analyzer Type	Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)
Incident Angle	not specified°
Emission Angle	not specified°
Analyzer Pass Energy:	160 eV
Analyzer Resolution	2.0 eV
Total Signal Accumulation Time	542 s
Total Elapsed Time	not specified
Number of Scans	2



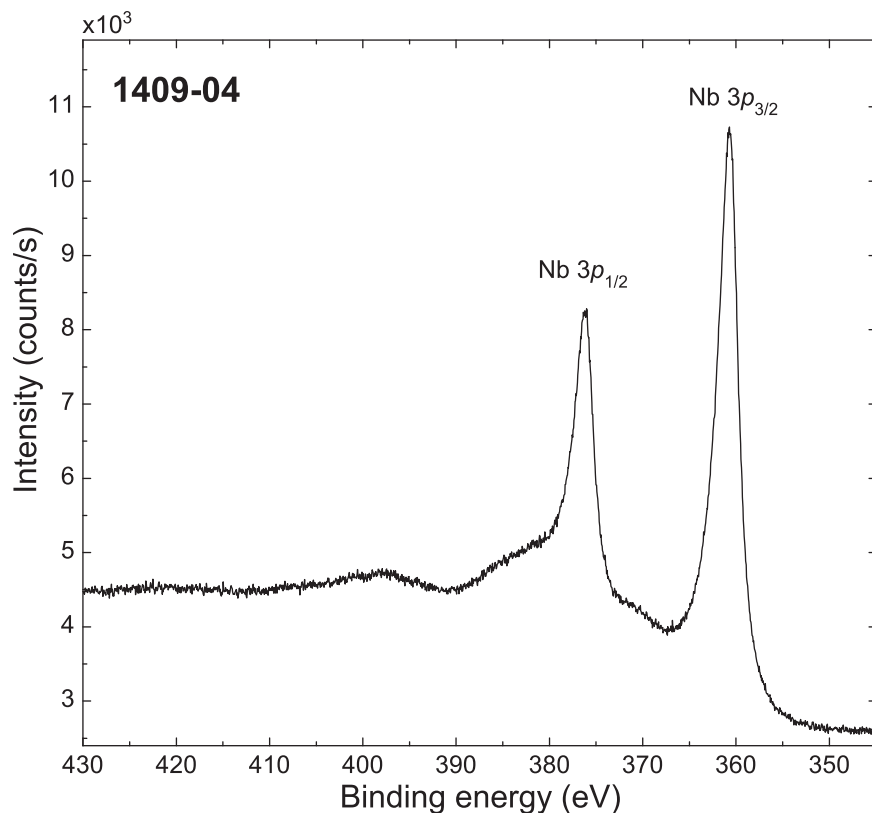
■ **Accession #:** 01409-02
 ■ **Host Material:** niobium
 ■ **Technique:** XPS
 ■ **Spectral Region:** Nb $3d_{3/2}$; Nb $3d_{5/2}$

Instrument: Kratos Analytical Axis Nova
 Excitation Source: Al K_{α} monochromatic
 Source Energy: 1486.6 eV
 Source Strength: 150 W
 Source Size: not specified
 Analyzer Type: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)
 Incident Angle: not specified°
 Emission Angle: not specified°
 Analyzer Pass Energy: 10 eV
 Analyzer Resolution: 0.53 eV
 Total Signal Accumulation Time: 587 s
 Total Elapsed Time: not specified
 Number of Scans: 2



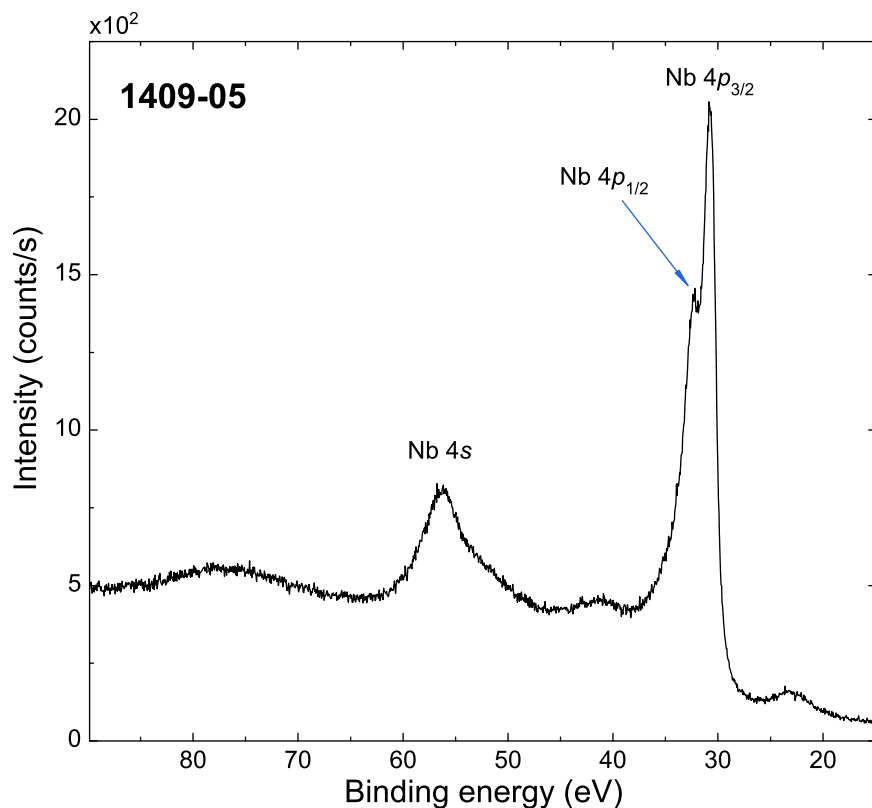
■ **Accession #:** 01409-03
 ■ **Host Material:** niobium
 ■ **Technique:** XPS
 ■ **Spectral Region:** Nb $3d_{3/2}$; Nb $3d_{5/2}$

Instrument: Kratos Analytical Axis Nova
 Excitation Source: Al K_{α} monochromatic
 Source Energy: 1486.6 eV
 Source Strength: 150 W
 Source Size: not specified
 Analyzer Type: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)
 Incident Angle: not specified°
 Emission Angle: not specified°
 Analyzer Pass Energy: 10 eV
 Analyzer Resolution: 0.53 eV
 Total Signal Accumulation Time: 1467 s
 Total Elapsed Time: not specified
 Number of Scans: 4



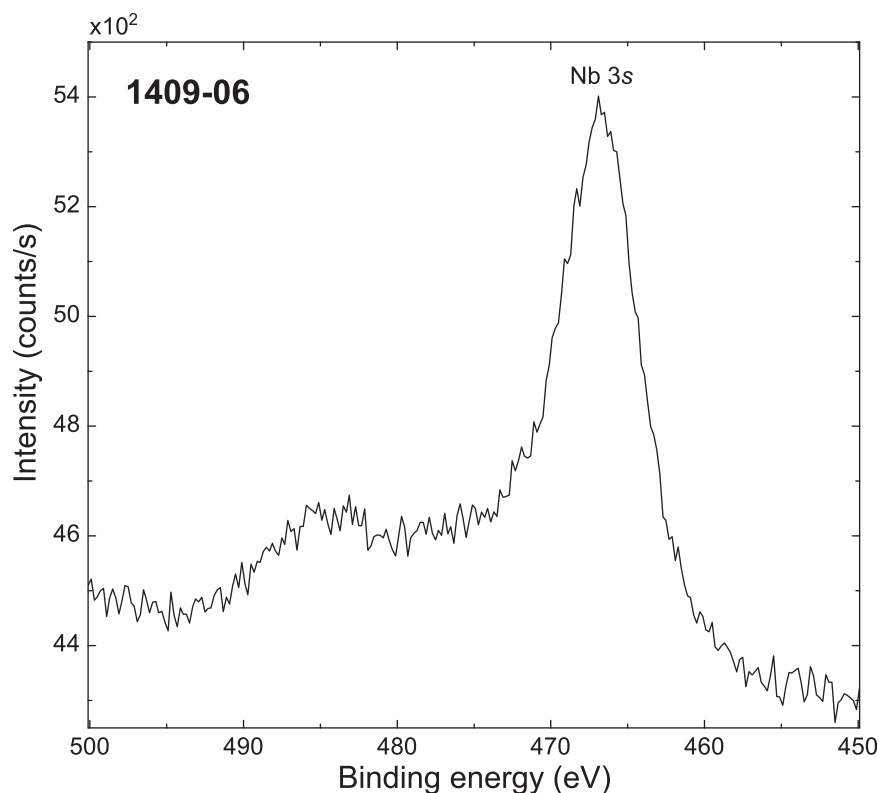
■ **Accession #:** 01409-04
 ■ **Host Material:** niobium
 ■ **Technique:** XPS
 ■ **Spectral Region:** Nb $3p_{1/2}$; Nb $3p_{3/2}$

Instrument: Kratos Analytical Axis Nova
 Excitation Source: Al K_{α} monochromatic
 Source Energy: 1486.6 eV
 Source Strength: 150 W
 Source Size: not specified
 Analyzer Type: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)
 Incident Angle: not specified°
 Emission Angle: not specified°
 Analyzer Pass Energy: 10 eV
 Analyzer Resolution: 0.53 eV
 Total Signal Accumulation Time: 4690 s
 Total Elapsed Time: not specified
 Number of Scans: 20



■ **Accession #:** 01409-05
 ■ **Host Material:** niobium
 ■ **Technique:** XPS
 ■ **Spectral Region:** Nb 4s; Nb $4p_{1/2}$; Nb $4p_{3/2}$

Instrument: Kratos Analytical Axis Nova
 Excitation Source: Al K_{α} monochromatic
 Source Energy: 1486.6 eV
 Source Strength: 150 W
 Source Size: not specified
 Analyzer Type: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)
 Incident Angle: not specified°
 Emission Angle: not specified°
 Analyzer Pass Energy: 10 eV
 Analyzer Resolution: 0.53 eV
 Total Signal Accumulation Time: 6004 s
 Total Elapsed Time: not specified
 Number of Scans: 20



■ **Accession #:** 01409-06
 ■ **Host Material:** niobium
 ■ **Technique:** XPS
 ■ **Spectral Region:** Nb 3s

Instrument: Kratos Analytical Axis Nova

Excitation Source: Al K_{α} monochromatic

Source Energy: 1486.6 eV

Source Strength: 150 W

Source Size: not specified

Analyzer Type: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)

Incident Angle: not specified^o

Emission Angle: not specified^o

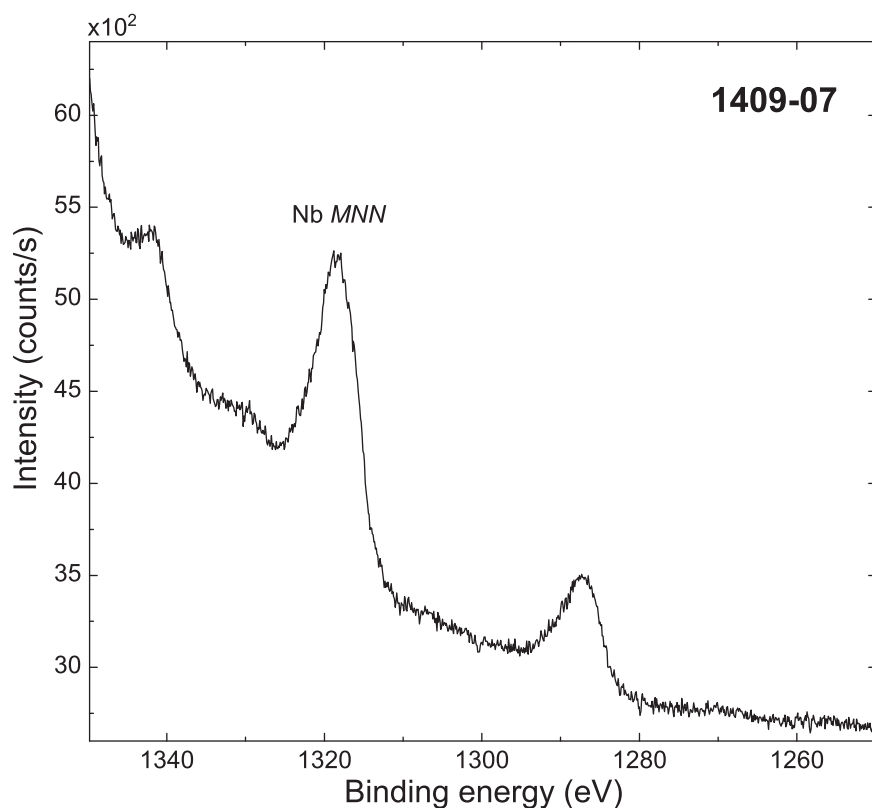
Analyzer Pass Energy: 10 eV

Analyzer Resolution: 0.53 eV

Total Signal Accumulation Time: 2408 s

Total Elapsed Time: not specified

Number of Scans: 80



■ **Accession #:** 01409-07
 ■ **Host Material:** niobium
 ■ **Technique:** XPS
 ■ **Spectral Region:** Nb MNN

Instrument: Kratos Analytical Axis Nova

Excitation Source: Al K_{α} monochromatic

Source Energy: 1486.6 eV

Source Strength: 150 W

Source Size: not specified

Analyzer Type: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)

Incident Angle: not specified^o

Emission Angle: not specified^o

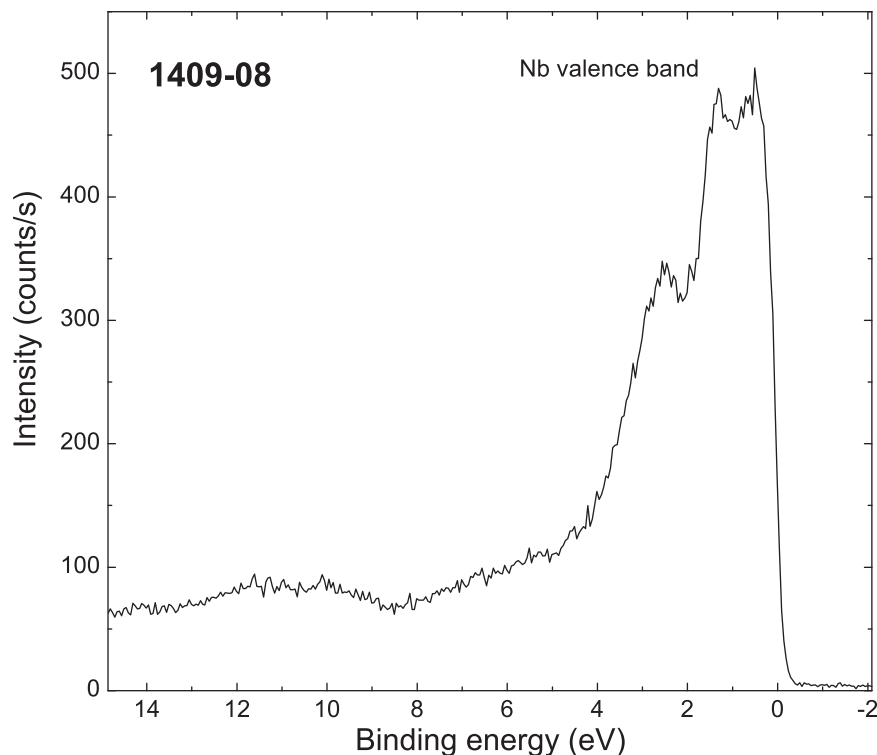
Analyzer Pass Energy: 10 eV

Analyzer Resolution: 0.53 eV

Total Signal Accumulation Time: 4004 s

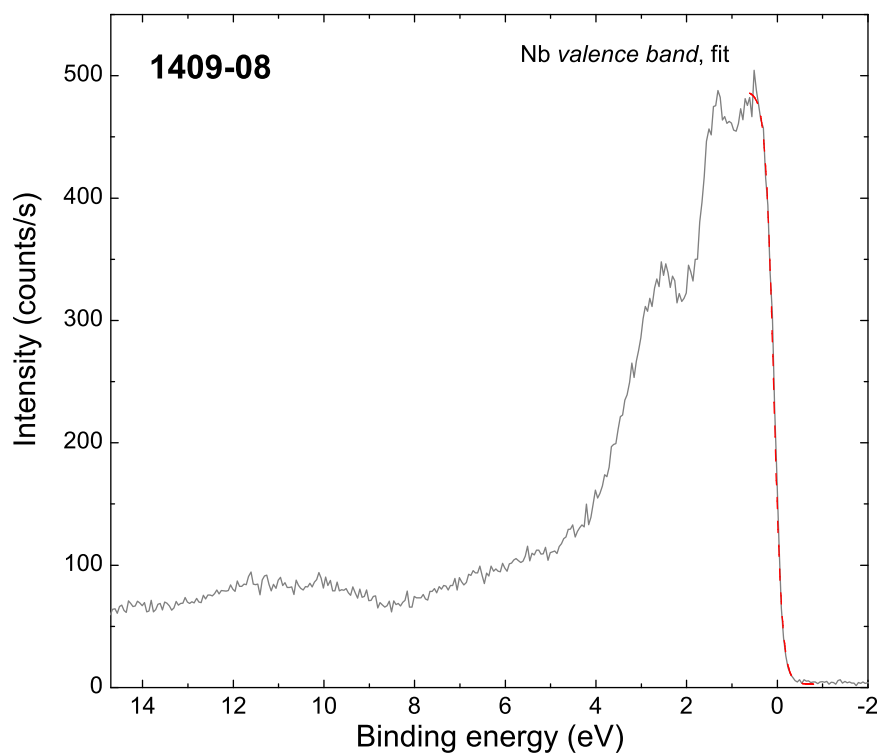
Total Elapsed Time: not specified

Number of Scans: 20



■ **Accession #:** 01409-08
 ■ **Host Material:** niobium
 ■ **Technique:** XPS
 ■ **Spectral Region:** Nb valence band

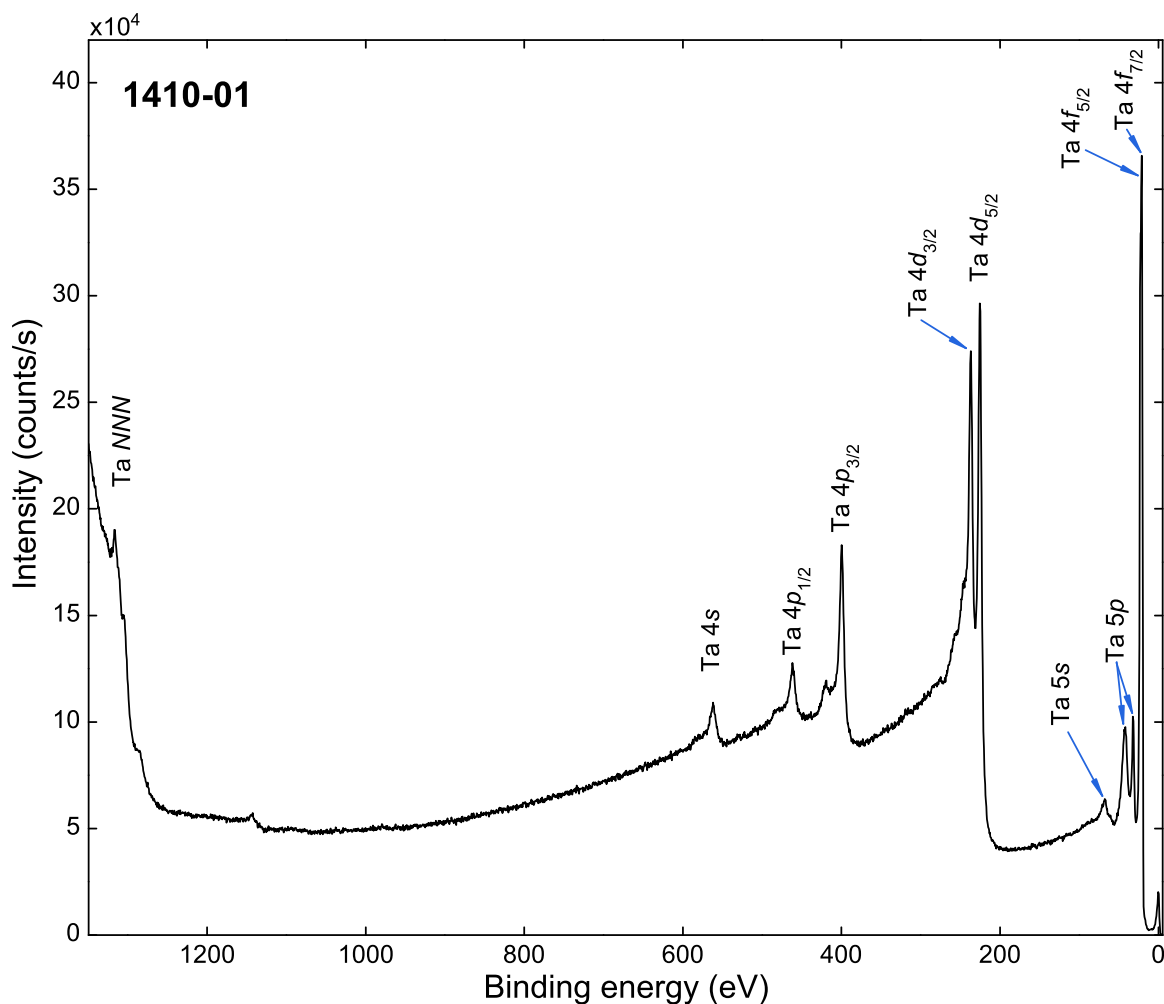
Instrument: Kratos Analytical Axis Nova
 Excitation Source: Al K_{α} monochromatic
 Source Energy: 1486.6 eV
 Source Strength: 150 W
 Source Size: not specified
 Analyzer Type: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)
 Incident Angle: not specified°
 Emission Angle: not specified°
 Analyzer Pass Energy: 10 eV
 Analyzer Resolution: 0.53 eV
 Total Signal Accumulation Time: 2046 s
 Total Elapsed Time: not specified
 Number of Scans: 30



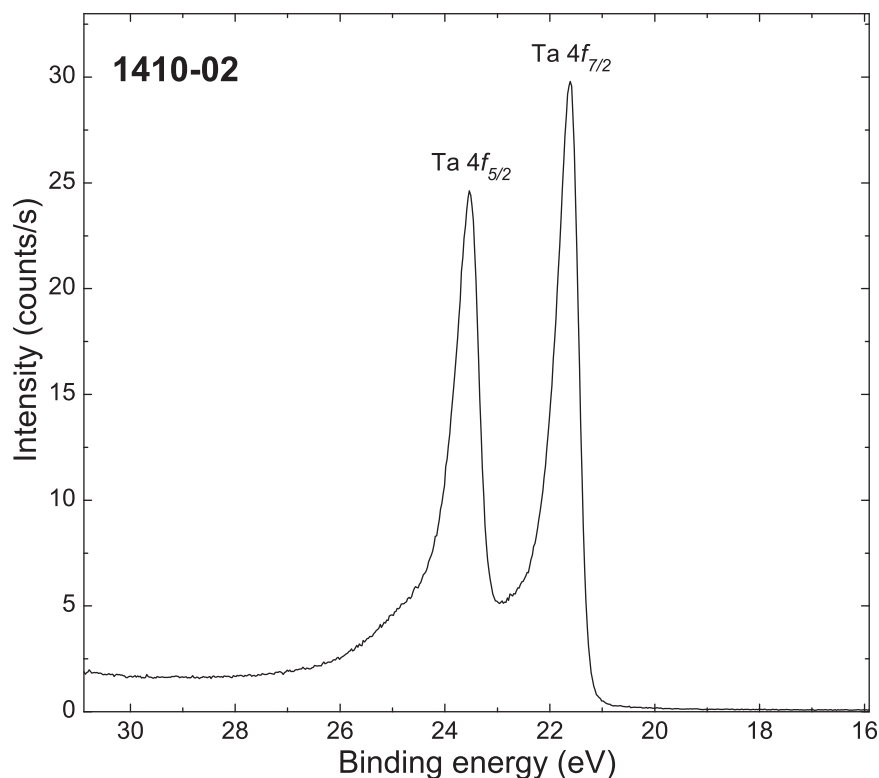
■ **Accession #:** 01409-08
 ■ **Host Material:** niobium
 ■ **Technique:** XPS
 ■ **Spectral Region:** Nb valence band

Instrument: Kratos Analytical Axis Nova
 Excitation Source: Al K_{α} monochromatic
 Source Energy: 1486.6 eV
 Source Strength: 150 W
 Source Size: not specified
 Analyzer Type: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)
 Incident Angle: not specified°
 Emission Angle: not specified°
 Analyzer Pass Energy: 10 eV
 Analyzer Resolution: 0.53 eV
 Total Signal Accumulation Time: 2046 s
 Total Elapsed Time: not specified
 Number of Scans: 30

Comment: Following figure shows Fermi function fit calibration reference. See Analyzer Calibration Table entry for Nb Fermi edge.

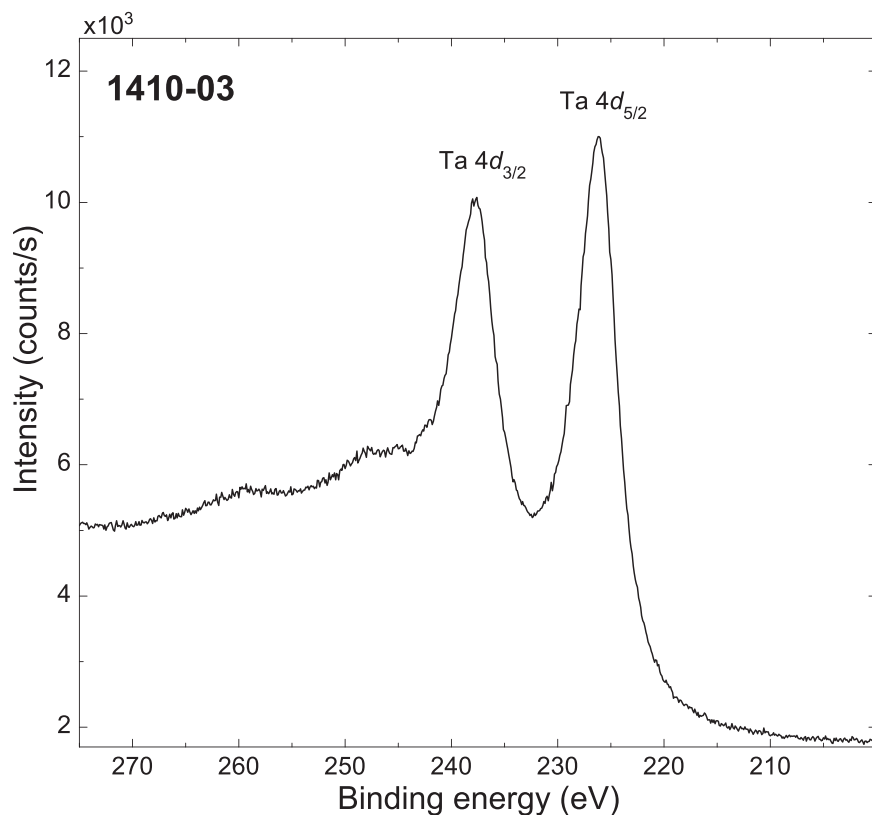


Accession #	01410-01
Host Material	tantalum
Technique	XPS
Spectral Region	survey
Instrument	Kratos Analytical Axis Nova
Excitation Source	Al K_{α} monochromatic
Source Energy	1486.6 eV
Source Strength	150 W
Source Size	not specified
Analyzer Type	Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)
Incident Angle	not specified°
Emission Angle	not specified°
Analyzer Pass Energy:	160 eV
Analyzer Resolution	2.0 eV
Total Signal Accumulation Time	271 s
Total Elapsed Time	not specified
Number of Scans	1



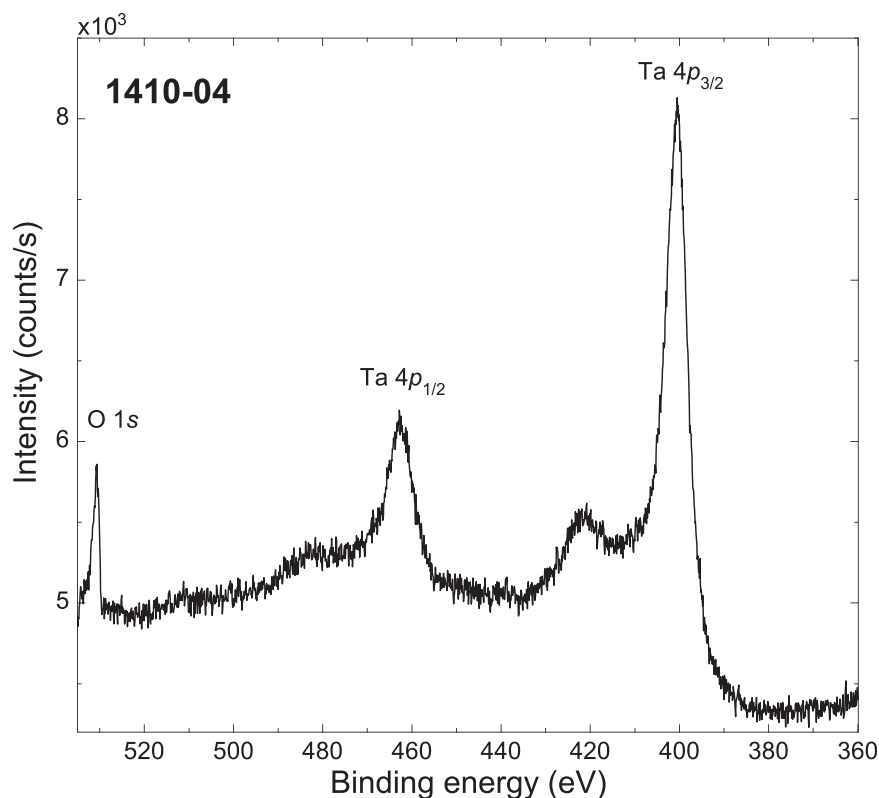
■ Accession #: [01410-02](#)
 ■ Host Material: tantalum
 ■ Technique: XPS
 ■ Spectral Region: Ta $4f_{5/2}$; Ta $4f_{7/2}$

Instrument: Kratos Analytical Axis Nova
 Excitation Source: Al K_{α} monochromatic
 Source Energy: 1486.6 eV
 Source Strength: 150 W
 Source Size: not specified
 Analyzer Type: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)
 Incident Angle: not specified°
 Emission Angle: not specified°
 Analyzer Pass Energy: 10 eV
 Analyzer Resolution: 0.53 eV
 Total Signal Accumulation Time: 551 s
 Total Elapsed Time: not specified
 Number of Scans: 2



■ Accession #: [01410-03](#)
 ■ Host Material: tantalum
 ■ Technique: XPS
 ■ Spectral Region: Ta $4d_{3/2}$; Ta $4d_{5/2}$

Instrument: Kratos Analytical Axis Nova
 Excitation Source: Al K_{α} monochromatic
 Source Energy: 1486.6 eV
 Source Strength: 150 W
 Source Size: not specified
 Analyzer Type: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)
 Incident Angle: not specified°
 Emission Angle: not specified°
 Analyzer Pass Energy: 10 eV
 Analyzer Resolution: 0.53 eV
 Total Signal Accumulation Time: 2635 s
 Total Elapsed Time: not specified
 Number of Scans: 16



■ **Accession #:** 01410-04
 ■ **Host Material:** tantalum
 ■ **Technique:** XPS
 ■ **Spectral Region:** O 1s; Ta 4p_{1/2}; Ta 4p_{3/2}

Instrument: Kratos Analytical Axis Nova

Excitation Source: Al K_α monochromatic

Source Energy: 1486.6 eV

Source Strength: 150 W

Source Size: not specified

Analyzer Type: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)

Incident Angle: not specified°

Emission Angle: not specified°

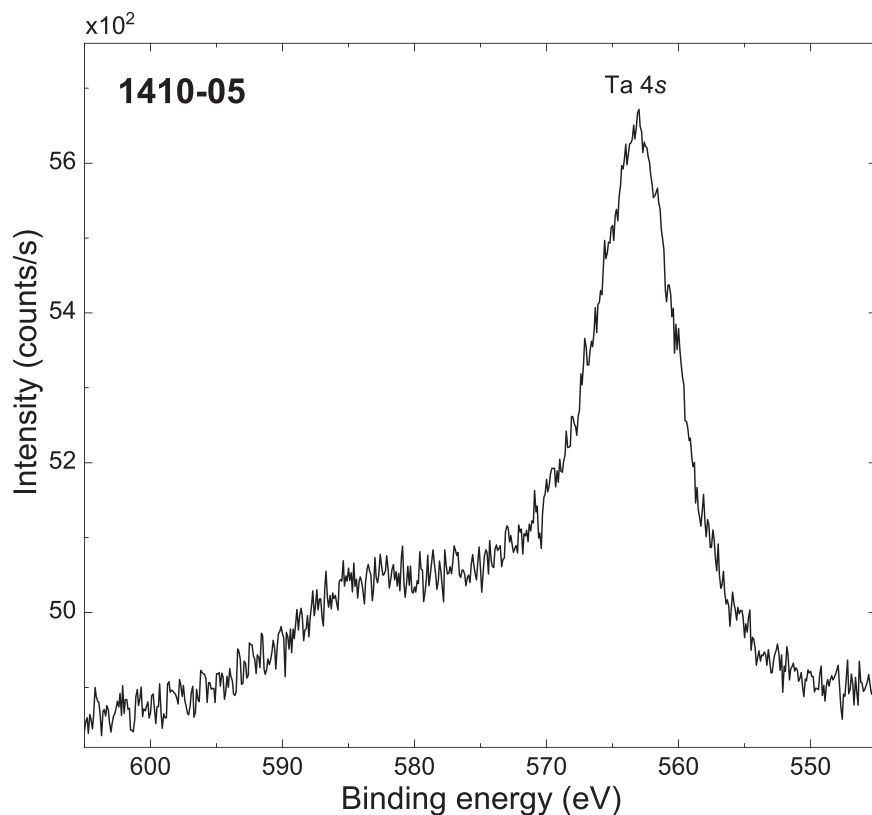
Analyzer Pass Energy: 10 eV

Analyzer Resolution: 0.53 eV

Total Signal Accumulation Time: 3226 s

Total Elapsed Time: not specified

Number of Scans: 26



■ **Accession #:** 01410-05
 ■ **Host Material:** tantalum
 ■ **Technique:** XPS
 ■ **Spectral Region:** Ta 4s

Instrument: Kratos Analytical Axis Nova

Excitation Source: Al K_α monochromatic

Source Energy: 1486.6 eV

Source Strength: 150 W

Source Size: not specified

Analyzer Type: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)

Incident Angle: not specified°

Emission Angle: not specified°

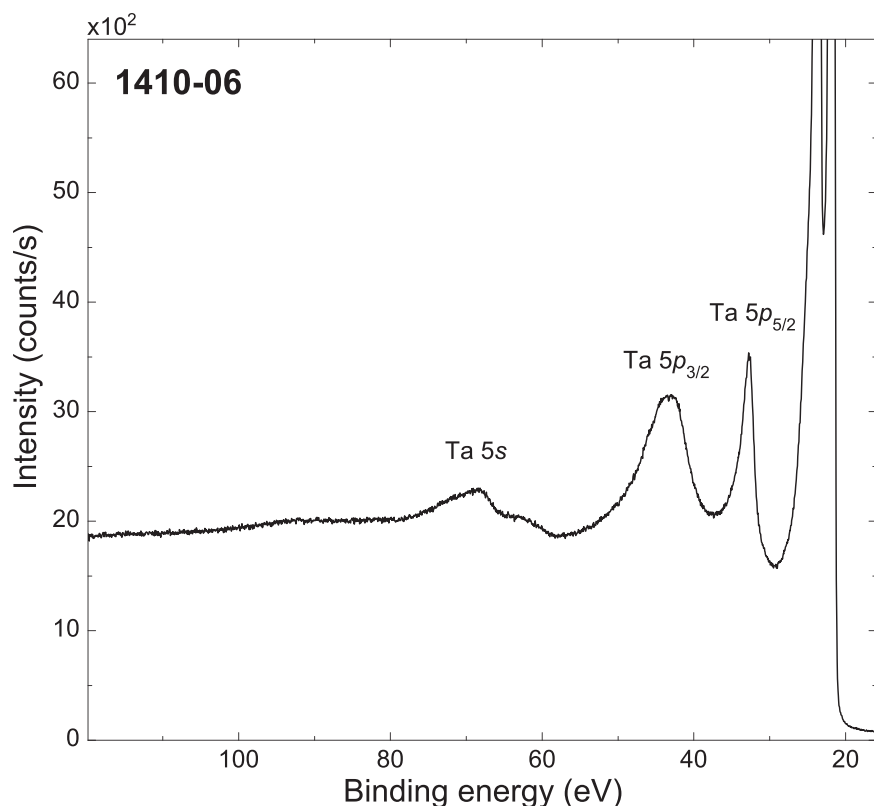
Analyzer Pass Energy: 10 eV

Analyzer Resolution: 0.53 eV

Total Signal Accumulation Time: 10217 s

Total Elapsed Time: not specified

Number of Scans: 64



■ **Accession #:** 01410-06
 ■ **Host Material:** tantalum
 ■ **Technique:** XPS
 ■ **Spectral Region:** Ta 5s; Ta 5p_{1/2}; Ta 5p_{3/2}

Instrument: Kratos Analytical Axis Nova

Excitation Source: Al K_α monochromatic

Source Energy: 1486.6 eV

Source Strength: 150 W

Source Size: not specified

Analyzer Type: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)

Incident Angle: not specified°

Emission Angle: not specified°

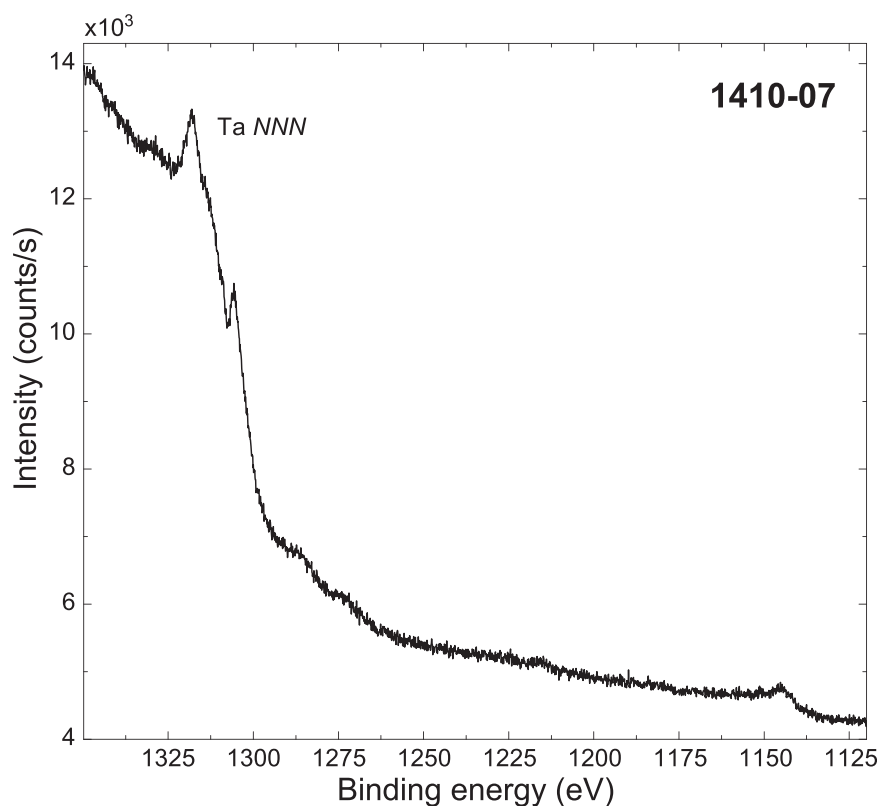
Analyzer Pass Energy: 10 eV

Analyzer Resolution: 0.53 eV

Total Signal Accumulation Time: 17156 s

Total Elapsed Time: not specified

Number of Scans: 18



■ **Accession #:** 01410-07
 ■ **Host Material:** tantalum
 ■ **Technique:** XPS
 ■ **Spectral Region:** Ta NNN

Instrument: Kratos Analytical Axis Nova

Excitation Source: Al K_α monochromatic

Source Energy: 1486.6 eV

Source Strength: 150 W

Source Size: not specified

Analyzer Type: Combined hemispherical analyzer (HSA) and spherical mirror analyzer (SMA)

Incident Angle: not specified°

Emission Angle: not specified°

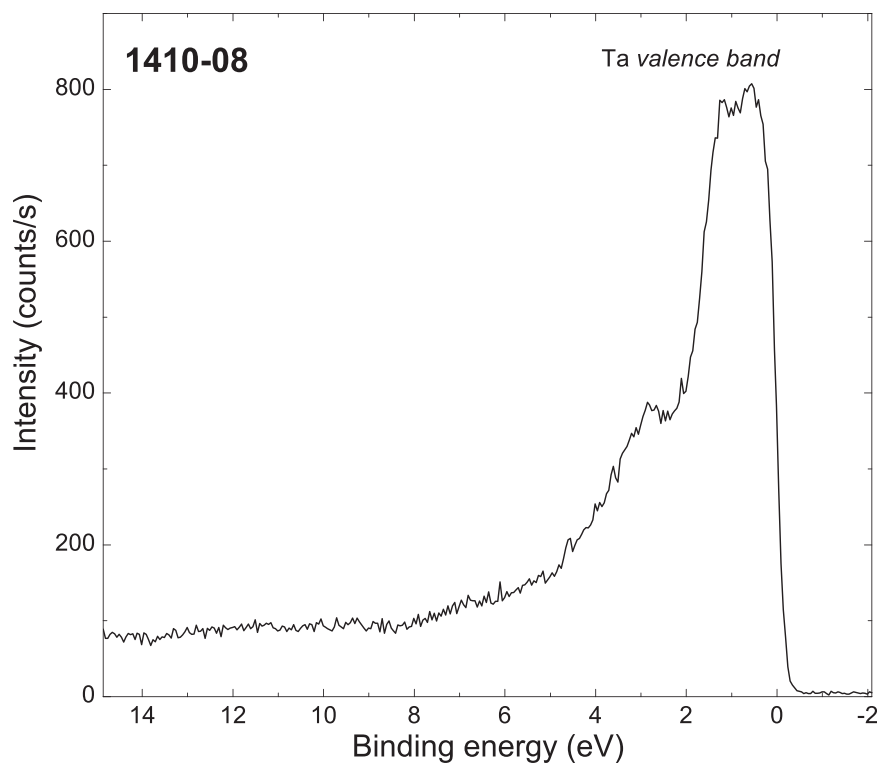
Analyzer Pass Energy: 10 eV

Analyzer Resolution: 0.53 eV

Total Signal Accumulation Time: 4142 s

Total Elapsed Time: not specified

Number of Scans: 18



■ **Accession #:** 01410-08
 ■ **Host Material:** tantalum
 ■ **Technique:** XPS
 ■ **Spectral Region:** Ta valence band

Instrument: Kratos Analytical Axis Nova

Excitation Source: Al K_{α}
 monochromatic

Source Energy: 1486.6 eV

Source Strength: 150 W

Source Size: not specified

Analyzer Type: Combined
 hemispherical analyzer (HSA) and
 spherical mirror analyzer (SMA)

Incident Angle: not specified°

Emission Angle: not specified°

Analyzer Pass Energy: 10 eV

Analyzer Resolution: 0.53 eV

Total Signal Accumulation Time: 1364 s

Total Elapsed Time: not specified

Number of Scans: 20

Comment: Following figure shows
 Fermi function fit calibration
 reference. See Analyzer Calibration
 Table entry for Ta Fermi edge.

